EUVL Supplier Showcase

Held Online, August 16-17, 2021

All Times are in US Central Time Zone (Austin, TX, USA). Netherlands is + 7 Hours and Korea / Japan are +14 Hours ahead.

Updated August 8, 2021

Session 1: US and Asia

6:30 PM, Monday, August 16, 2021, Austin, TX, USA (8:30 AM, Tuesday, August 17, Korea and Japan)

Please see Abstract Book on website for abstracts and co-author (s) information by paper #.

Paper #	Presenter	Company	Title	Duration	Start	Finish
			AV-Test and Speaker check-in	0:30	6:30 PM	7:00 PM
Intro	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements	0:05	7:00 PM	7:05 PM
			Keynote			
SS1	Debbie Gustafson	Energetiq	Building a Success Company in EUVL - Growth of Energetiq Technology, Inc.	0:30	7:05 PM	7:35 PM
			Non- Profit Organizations			
SS2	Jinho Ahn	EUV-IUCC	Recent research activities in EUV-IUCC (Industry-University Collaboration Center)	0:15	7:35 PM	7:50 PM
SS4	Sangsul Lee	Pohang Accelerator Laboratory	PAL-EUV synchrotron construction progress and EUV infrastructure operation plan	0:15	7:50 PM	8:05 PM
SS5	Ryan Miyakawa	CXRO	Preparing For The Next Generation of EUV Lithography at the Center for X-ray Optics	0:15	8:05 PM	8:20 PM
			Break	0:20	8:20 PM	8:40 PM
			Suppliers			
SS15	Warren Montgomery	IM	Multitrigger (MTR): An Irresistible Photoresist	0:15	8:40 PM	8:55 PM
SS16	Sung Park	Molecuar Vista	IR PiFM – Potential for EUV Metrology	0:15	8:55 PM	9:10 PM
SS24	Matthew Harada	K&M Lab	Developments in KMLabs EUV Laser sources	0:15	9:10 PM	9:25 PM
SS23	Supriya Jaiswal	Astrileux	Product Differentiation in EUV Photomasks	0:15	9:25 PM	9:40 PM
SS6	Yusuke Suzuki	Dai Nippon Printing	EUV Mask Technology: Ready for 5nm and beyond	0:15	9:40 PM	9:55 PM
SS7	Sung Won Choi	FST	Automated EUV tools for HVM – Pellicle Mounter/Demounter, Pellicle & Pod Inspection Systems	0:15	9:55 PM	10:10 PM
			End Session 1			

Session 2: Europe and US

7:30 AM, Tuesday, August 17, 2021, Austin, TX, USA

(9:30 PM, Tuesday, August 17, Korea and Japan)

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			AV-Test and Speaker check-in	0:30	7:30 AM	8:00 AM
Intro	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements	0:05	8:00 AM	8:05 AM
			Non- Profit Organizations			
SS8	Iacopo Mochi	PSI	EUV interference lithography and metrology at PSI	0:15	8:05 AM	8:20 AM
SS9	Michael Kolbe	PTB	Synchrotron-radiation based EUV metrology at PTB	0:15	8:20 AM	8:35 AM
SS10	Norbert Koster	TNO	TNO, R&D service provider for the EUV Semiconductor Industry	0:15	8:35 AM	8:50 AM
SS11	Vieker, Jochen	Fraunhofer	Irradiation systems for accelerated testing of EUVL components	0:15	8:50 AM	9:05 AM
SS12	Charles Tarrio	NIST	NIST at-wavelength EUVL metrology	0:15	9:05 AM	9:20 AM
SS3	Satinder Sharma	IIT Mandi	Resist Technology for Single Digit Patterning: A solution for High-volume & High-throughput EUVL	0:15	9:20 AM	9:35 AM
			Break	0:20	9:35 AM	9:55 AM
			Suppliers			
SS17	Philipp Naujok	optiXfab	The art of fabricating high reflective multilayer coatings	0:30	9:55 AM	10:25 AM
SS18	Peter Oberta	Rigaku Innovative Technologies Europe s.r.o.	Rigaku EUV optics and detector technology	0:15	10:25 AM	10:40 AM
SS19	Slava Medvedev	RnD ISAN	TEUS - high-brightness EUV LPP light source based on fast rotating target: product overview and specifications	0:15	10:40 AM	10:55 AM
SS20	Marcel Demmler	Scia Systems	Vacuum Processing Equipment for EUVL Optics - deposition, etching and cleaning	0:15	10:55 AM	11:10 AM
SS13	Christopher Metting	Accustrata	AtOMS - Combined Atomic Absorption /Optical Emission Spectroscopy for In-Situ Control of EUVL Thin Films	0:15	11:10 AM	11:25 AM
SS21	Meng Lee	Veeco	Veeco Ion Beam Technology for EUV Mask	0:15	11:25 AM	11:40 AM

End Session 2

Workshop Adjourned